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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q77049

Kesahiro KOIKE, et al.

Appln. No.: 10/642,657

Group Art Unit: 1756

Confirmation No.: 3050

Examiner: John S. Ruggles

Filed: August 19, 2003

For: METHOD OF PRODUCING A GLASS SUBSTRATE FOR A MASK BLANK,
METHOD OF PRODUCING A MASK BLANK, METHOD OF PRODUCING A
TRANSFER MASK, METHOD OF PRODUCING A SEMICONDUCTOR DEVICE,
GLASS SUBSTRATE FOR A MASK BLANK, MASK BLANK, AND TRANSFER
MASK

PETITION FOR EXTENSION OF TIME UNDER 37 C.F.R. § 1.136

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. § 1.136, Applicant hereby petitions for an extension of time of one month, extending the time for responding to the Office Action of August 26, 2005 to December 26, 2005.

A check for the statutory fee of \$120.00 is attached. The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account. A duplicate copy of this sheet is enclosed.

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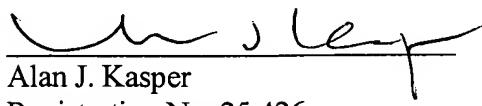
WASHINGTON OFFICE

23373

CUSTOMER NUMBER

Date: December 27, 2005

Respectfully submitted,



Alan J. Kasper
Registration No. 25,426